



## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re U.S. Patent Application

Applicant: Satoshi Kitagawa

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I hereby certify deposited with serial No.: 09/696,117

Serial No.: 09/696,117

Commissioner

Filed: October 25, 2000

For: MARKING METHOD FOR SEMICONDUCTOR WAFER

Gerald T. Shelp

Karl D. Frech

on October 4, 2002.

Shall Shelleton Reg. No. 27,466

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to:

Commissioner of Patents, Washington, DC 20231,

**AMENDMENT** 

Box NON-FEE AMENDMENT Commissioner for Patents , Washington, D.C. 20231

Dear Sir:

Examiner:

The Office Action of February 5, 2002 has been carefully reviewed and the following amendments and remarks are made in response thereto:

## IN THE CLAIMS:

Please amend claims 5, 6, 10, 11, and 17 to 22 as follows:

5. (Amended) The method of reproducing a mark on a semiconductor wafer according to claim 2, wherein the predetermined mark is formed by means of a combination of dots, each dot measuring 1 to 13 µm wide, and the substantially-effaced mark is reproduced by means of forming a mark essentially identical with the substantially-effaced mark at another location in the vicinity fo the

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110.60 CH (Amended) The method of reproducing a mark on a semiconductor wafer according to claim 2, wherein the predetermined mark is a minute ID mark which is assigned to the semiconductor wafer and is formed by means of a combination of dots, each dot measuring 1 to 13 µm wide, and the substantially-effaced mark is reproduced by means of forming a mark essentially identical with the substantially-effaced mark at another location in the vicinity of the substantially-effaced mark.

1